

**Notice of References Cited**

Application/Control No.

10/529,234

Applicant(s)/Patent Under  
Reexamination  
WARD-CLOSE ET AL.

Examiner

CHRISTOPHER KESSLER

Art Unit

1793

Page 1 of 1

**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-4,602,947	07-1986	McClincy et al.	75/338
	B	US-			
	C	US-			
	D	US-			
	E	US-			
	F	US-			
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	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

**FOREIGN PATENT DOCUMENTS**

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**NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Mac Rae, "Plasma ARC Process System, Reactors, and Applications", Plasma Chemistry and Plasma Processing, Plenum Press, New York, 9(1) SUPPL:85S-118 (1989)
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\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.